



제 29회 한국반도체학술대회

The 29th Korean Conference on Semiconductors

2022년 1월 24일(월)~ 26일(수) | 강원도 하이원 그랜드호텔(컨벤션타워)

2022년 1월 25일(화), 16:00-17:45

Room B (에메랄드 II+III, 5층)

D. Thin Film Process Technology 분과

[TB3-D] Thin Films Process I

좌장: 이용규 교수(명지대학교), 엄태용 선임(KRICT)

<p>TB3-D-1 16:00-16:30</p>	<p>Atomic Craft of Materials Enabled by Atomic Layer Deposition for Electronics and Energy Applications Byung Joon Choi <i>Department of Materials Science and Engineering, Seoul National University of Science and Technology</i></p>
<p>TB3-D-2 16:30-16:45</p>	<p>Thermoelectric Performance Enhancement by Insertion of ZnO Thin Film on SnSe Powders Myeong Jun Jung, Ye Bin Weon, Ji Young Park, Ye Jun Yun, Jongmin Byun, and Byung Joon Choi <i>Department of Materials Science and Engineering, Seoul National University of Science and Technology</i></p>
<p>TB3-D-3 16:45-17:00</p>	<p>Atomic Layer Deposition of TiO₂ Thin Films Using a Novel Ti-precursor, CpTi(OⁱBu)₃, for DRAM Capacitors on Various Substrates Jonghyun Kim¹, Daeun Lim¹, Yeji Lee¹, Yumi Wang², Hongseok Jang², Suhyong Yun², and Woongkyu Lee¹ <i>¹Myongji University, ²Oceanbridge Co., Ltd.</i></p>
<p>TB3-D-4 17:00-17:15</p>	<p>PEALD with Post-Treatments for Interface Improvement of HfO₂-Based Metal-Insulator-Semiconductor Structures Jongseo Park¹, Kyeong-keun Choi², Bohyeon Kang¹, Jehyun An¹, and Rock-Hyun Baek¹ <i>¹Department of Electrical Engineering, POSTECH, ²National Institute for Nanomaterials Technology (NINT), POSTECH</i></p>
<p>TB3-D-5 17:15-17:30</p>	<p>Atomic Layer Deposition of GeTe/Sb₂Te₃ Superlattice for Large-Capacity and Low-Power Phase Change Memory Chanyoung Yoo¹, Jeong Woo Jeon¹, Woohyun Kim¹, Wonho Choi¹, Byongwoo Park¹, Gwangsik Jeon¹, Sangmin Jeon¹, Yoon Kyeung Lee², and Cheol Seong Hwang¹ <i>¹Department of Materials Science and Engineering and Inter-University Semiconductor Research Center, Seoul National University, ²Division of Advanced Materials Engineering, Jeonbuk National University</i></p>
<p>TB3-D-6 17:30-17:45</p>	<p>Adsorption Mechanism of Dimethylaluminum Isopropoxide on Al₂O₃ Sehee Kim, Miso Kim, and Bonggeun Shong <i>Chemical Engineering, Hongik University</i></p>